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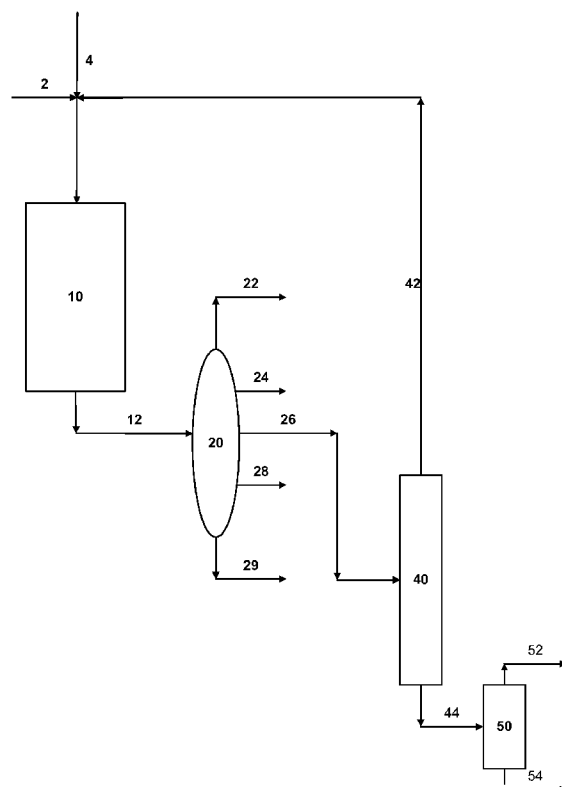
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[Continued on next page]

(54) Title: PROCESS FOR THE PRODUCTION OF PARA-XYLENE

Figure 1



(57) Abstract: A reforming process using a medium pore zeo-
 lite under conditions to facilitate the conversion of C₈ paraf-
 finic compounds to para-xylene is provided. Para-xylene is
 produced at greater than thermodynamic equilibrium concen-
 trations using the process.



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